

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Seok-Yoon YANG, et al.)
Serial No.: 10/675,455) Group Art Unit: 1795
Filed: September 30, 2003)
For: PHOTOSENSITIVE RESIN COMPOSITION) Examiner:
CONTROLLING SOLUBILITY AND PATTERN) Walke, Amanda C.
FORMATION METHOD OF DOUBLE-LAYER) Confirmation No. 5598
STRUCTURE USING THE SAME)

OK TO ENTER: /ACW/

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

11/18/2008

**RESPONSE TO FINAL OFFICE ACTION
UNDER 37 CFR § 1.116, WITH AMENDMENT**

Dear Sir:

In response to the Final Office action mailed on July 10, 2008, Applicants request reconsideration in view of the following remarks for entry in the above-identified application. This reply is being submitted with a Petition of one-month extension of time. Please charge an appropriate extension fee to Deposit Account No. 06-1130.

Listing of the Claims currently on file begins on page 2 of this paper; and
Remarks begin on page 6 of this paper.

Attachments: Certified English translation for Korean Patent Application No. 10-2002-0060500 filed on October 4, 2002.